

Special Issue

Advances in Ferroelectric Materials and Devices: Developments and Prospects

Message from the Guest Editors

The aim of this Special Issue is to highlight the most recent advancements in the science and technology of ferroelectric materials, such as Hafnium oxide (HfO₂) and Aluminum scandium nitride (AlScN), covering broad range of fields from the material process to the development of new devices and their applications through a combination of original research papers and review articles from leading groups around the world. In particular, the topics of interest include but are not limited to:

- Advancements in ferroelectric thin films, growth, and characterization;
- Novel ferroelectric thin films for capacitors and their applications;
- Ferroelectric memory devices (FTJ, FeRAM, FeFETs, etc.);
- DRAM cell capacitors and Morphotropic Phase Boundary (MPB);
- Anti-ferroelectric thin film devices for Energy Storage Technology;
- Ferroelectric thin films for imprint technology;
- Ferroelectric thin films for sensors, actuators, and energy-harvesting devices;
- Ferroelectric thin films for Neuromorphic Devices.

Guest Editors

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Message from the Editor-in-Chief

As the world of science becomes ever more specialized, researchers may lose themselves in the deep forest of the ever increasing number of subfields being created. This open access journal Applied Sciences has been started to link these subfields, so researchers can cut through the forest and see the surrounding, or quite distant fields and subfields to help develop his/her own research even further with the aid of this multi-dimensional network.

Editor-in-Chief

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